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RESPONSE UNDER 37 CFR 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 1700

PATENT
Attorney Docket No. 98124X205843
Client Reference No. 98124CON2

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Wang et al.

Application No. 09/636,246

Filed: August 10, 2000

For: POLISHING SYSTEM WITH
STOPPING COMPOUND AND
METHOD OF ITS USE

Art Unit: 1765

Examiner: Charlotte A. Brown

RESPONSE TO OFFICE ACTION

Commissioner for Patents
Box AF
Washington, D.C. 20231

Dear Sir:

In response to the Office Action dated November 19, 2002, please enter the following amendments and consider the following remarks.

AMENDMENTS

IN THE CLAIMS:

Replace the indicated claims with:

C1

1. (Amended) A system for polishing one or more layers of a multi-layer substrate that includes a first metal layer and a second layer comprising (i) a liquid carrier, (ii) at least one oxidizing agent, (iii) at least one polishing additive that increases the rate at which the system polishes at least one layer of the substrate, (iv) at least one stopping compound with a polishing selectivity of the first metal layer:second layer of at least about 30:1, wherein the stopping compound is a cationically charged nitrogen containing compound selected from the group consisting of a polyetheramine, polyethylenimine, N₄-amino(N,N'-bis-[3-aminopropyl]ethylenediamine), 4,7,10-trioxatridecane-1,13-diamine,

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02 FC:2202 54.00 CH

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